

**REMARKS**

At the outset, the Examiner is thanked for the thorough review and consideration of the pending application. The Office Action dated May 28, 2008, has been received and its contents carefully reviewed.

By this response, claims 13, 23 and 28 are hereby amended. No new matter is added. Accordingly, claims 13, 16, 18, 23-25, 28-30 and 32-37 are currently pending. Reexamination and reconsideration of the pending claims is respectfully requested.

In the Office Action, Claims 13, 16, 18, 23-25, 28-30 and 32-37 are rejected under 35 U.S.C. § 103(a) as being unpatentable over Moinpour et al. (U.S. Patent No. 5,901,399, hereinafter “Moinpour”) in view of Fishkin et al. (U.S. Patent No. 6,202,658, hereinafter “Fishkin”) and Hashimoto et al. (U.S. Patent No. 6,261,378, hereinafter “Hashimoto”).

Applicants respectfully traverse the rejection and reconsideration is respectfully requested. In particular, Applicants submit independent claim 13 is allowable at least in that claim recites, inter alia, “a fourth step, jetting deionized water at high pressure...and wherein the jetting of deionized water is performed to the side surface of the substrate that the brushing of a side surface is completed”.

Applicants further submit independent claim 23 is allowable at least in that claim 23 recites, inter alia, “...by jetting deionized water at high pressure...and wherein the jetting of deionized water is performed to the side surface of the substrate that the brushing of a side surface is completed”.

Applicants further submit independent claim 28 is allowable at least in that claim recites, inter alia, “fourth step, spraying water at high pressure...and wherein the spraying of water is performed to the side surface of the substrate that the brushing of a least two opposing side surfaces is completed”.

In Mainpour, edge cleaning apparatus 204 is provided such that side surface of wafer 202 is cleaned only at one time.

In Fishkin, sonic edge nozzle 35 is provided such that side surface of wafer 202 is cleaned only at one time.

On the contrary, side cleaning brushes 32 and a sonar 38 are provided to clean side surface of a substrate in the claimed invention.

Thus, in the claimed invention, the side surface of a substrate is cleaned two times, whereby particles attached to the side surface are completely removed. Additionally, in the claimed invention, after the brushing process is performed, a jetting process is performed, whereby particles not removed by the brushing process are completely removed by the jetting at high pressure.

Based upon the above, Applicants submit the cited references, analyzed singly or in combination, fail to teach or suggest at least this feature of the claimed invention.

Accordingly, Applicant respectfully submits that claims 13, 23 and 28 and claims 16, 18, 24-25, 29-30 and 32-37, which respectively depend therefrom, are allowable over the cited references.

Applicants believe the foregoing amendments and remarks place the application in condition for allowance and early, favorable action is respectfully solicited.

If for any reason the Examiner finds the application other than in condition for allowance, the Examiner is requested to call the undersigned attorney at (202) 496-7500 to discuss the steps necessary for placing the application in condition for allowance. All correspondence should continue to be sent to the below-listed address.

If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. § 1.136, and any additional fees required under 37 C.F.R. § 1.136 for any necessary extension of time, or any other fees required to complete the filing of this response, may be charged to Deposit Account No. 50-0911.

Please credit any overpayment to deposit Account No. 50-0911.

Respectfully submitted,

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